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APPLICATION NO.	FII	LING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/695,724	10/28/2003		Eric Frayssinet	15675P314CX	5542
8791	7590	02/24/2005		EXAM	MINER
BLAKELY 12400 WILS		OFF TAYLOR &	LEE, HS	LEE, HSIEN MING	
SEVENTH I			ART UNIT	PAPER NUMBER	
LOS ANGELES, CA 90025-1030				2823	

DATE MAILED: 02/24/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
Office Astion Comments	10/695,724	FRAYSSINET ET AL.				
Office Action Summary	Examiner	Art Unit				
	Hsien-ming Lee	2823				
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a repl - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailin earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be tim y within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from e, cause the application to become ABANDONE	ely filed s will be considered timely. the mailing date of this communication. O (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on	<u>_</u> .					
2a) ☐ This action is <b>FINAL</b> . 2b) ☒ This	action is non-final.					
3) Since this application is in condition for allowa	) Since this application is in condition for allowance except for formal matters, prosecution as to the ments is					
closed in accordance with the practice under E	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims						
4)⊠ Claim(s) <u>1-20</u> is/are pending in the application.						
	4a) Of the above claim(s) is/are withdrawn from consideration.					
5) Claim(s) is/are allowed.						
6) Claim(s) is/are rejected.	Claim(s) is/are rejected.					
7) $\boxtimes$ Claim(s) <u>1-20</u> is/are objected to.						
8) Claim(s) are subject to restriction and/o	or election requirement.					
Application Papers						
9)⊠ The specification is objected to by the Examine	er.					
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
Applicant may not request that any objection to the	drawing(s) be held in abeyance. See	37 CFR 1.85(a).				
Replacement drawing sheet(s) including the correct	• • • • • • • • • • • • • • • • • • • •	• •				
11) The oath or declaration is objected to by the Ex	xaminer. Note the attached Office	Action or form PTO-152.				
Priority under 35 U.S.C. § 119						
12)⊠ Acknowledgment is made of a claim for foreign a)⊠ All b)□ Some * c)□ None of:	priority under 35 U.S.C. § 119(a)	-(d) or (f).				
1. Certified copies of the priority documents have been received.						
2. Certified copies of the priority document		on No. <u>09/530,050</u> .				
3. Copies of the certified copies of the prio	rity documents have been receive	d in this National Stage				
application from the International Burea	, ,,					
* See the attached detailed Office action for a list	of the certified copies not receive	d. HSIEN-MING LI				
		DOINGADO EVALUI				
Amazhar antia)		(PTO-413)				
Attachment(s)  1) X Notice of References Cited (PTO-892)	4) 🔲 Interview Summary	(PTO-413)				
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail Da	te				
<ol> <li>Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)</li> <li>Paper No(s)/Mail Date <u>122403</u>.</li> </ol>	5) Notice of Informal Po	atent Application (PTO-152)				

### **DETAILED ACTION**

## Claim Objections

1. Claims 1, 3, 5-10 are objected to because of the following informalities: in-consistent term.

In claim 1, at line 6, changing "gallium nitride" into – continuous gallium nitride –; and at line 8, changing "gallium nitride" into – continuous gallium nitride layer – are suggested.

In claim 3 (line 1), claim 8 (line 1), claim 9 (line 4), changing "silicon nitride layer" into

- silicon nitride film - is suggested.

In claim 5, claim 6 (line 3), claim 9 (line 3), changing "gallium nitride layer" into – continuous gallium nitride layer –is suggested.

In claim 7 and claim 9 (line 4), the term "the carrier gas" lacks antecedent basis.

In claim 10, at line 2, changing "consisting in" into – consistent of – is suggested.

### Specification

2. The disclosure is objected to because of the following informalities: typographical error.

On page 12, paragraph [0055], at line 7, changing "(Fig.2" into – (Fig.2) – is suggested.

Appropriate correction is required.

### Allowable Subject Matter

- 3. Claim 1 would be allowable if rewritten or amended to overcome the objection, set forth in this Office action.
- 4. Claims 3 and 5-10 would be allowable if rewritten to overcome the objection, set forth in this Office action and to include all of the limitations of the base claim and any intervening claims.

Application/Control Number: 10/695,724

Art Unit: 2823

5. Claims 2, 4, and 11-20 are objected to as being dependent upon an objected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Page 3

6. The following is a statement of reasons for the indication of allowable subject matter:

Letertre et al. to US 6,794,276 teach forming a silicon nitride film 10/11 on a substrate 12; forming a seed layer of monocrystalline gallium nitride 2 and forming a working layer of gallium nitride 16, which is formed by CVD or MBE or hydride vapor phase epitaxy (HVPE) (Fig. 2 and col. 7, lines 1-40).

Urashima et al. to US 6,852,161 teach forming a silicon nitride film 5 (i.e. a mask layer) at a temperature at least 1000 °C (col. 18, lines 20-21 and 45-48 and Fig.9(b)) on a substrate 1; forming a gallium nitride 8 on an exposed portion of the substrate 1 (Fig.9(d)) and after forming the silicon nitride (i.e. mask layer) 5 reducing the substrate temperature to 1180 °C and providing TMG vapor to form gallium nitride layer 9 on the silicon nitride 5 (Fig.9(g) and col. 44, lines 47-53).

In contrast, the prior art of record neither teaches nor suggests depositing a silicon nitride film of between 5 to 20 monolayers; depositing a continuous gallium nitride on the silicon nitride at a temperature ranging from 400 to 600  $^{\circ}$ C; and annealing the gallium nitride layer at a temperature ranging form 950 to 1120  $^{\circ}$ C; and performing an epitaxial regrowth with the gallium nitride layer at the end of a spontaneous in situ formation of islands of gallium nitride.

7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hsien-ming Lee whose telephone number is 571-272-1863. The examiner can normally be reached on Tuesday-Thursday ( $8:00 \sim 6:00$ ).

Art Unit: 2823

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on 571-272-1855. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

> Hsien-ming Lee Primary Examiner Art Unit 2823

> > HSIEN-MING LEE PRIMARY EXAMINE

Feb 22, 2005